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Optical Emission Spectroscopy of Nitrogen Gas in the High Frequency Single and Dual RF-PECVD[1] DEMIRAL AKBAR, Plasma Physics — High frequency single and dual RF capacitive coupled plasma enhanced chemical vapor depositions have been investigated using Optical Emission Spectroscopy (OES) of pure nitrogen gas. Two RF sources (40.68MHz on the top electrode, and 2.1 MHz on the bottom electrode) are coupled to each other through the plasma medium. It was found that the ionization density of the working gas in the dual RF-PECVD is higher than that obtained using HF single RF-PECVD discharge alone.

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